

**Session Code [09] ThJ2**

<b>Session Title</b>	Ferroelectric Materials and Devices 2
<b>Date and Time</b>	Thursday, October 7, 2021 / 14:00-15:20
<b>Session Room</b>	Room J (401)
<b>Session Chair(s)</b>	Jung Ho Yoon (KIST, Korea) Uwe Schroeder (NaMLab gGmbH, Germany)

**[[09] ThJ2-1] Invited Talk [Online] 14:00-14:25****Ultrathin Ferroelectricity and Its Application in Advanced Logic and Memory Devices**Sayeef Salahuddin (*Univ. of California, Berkeley, USA*)**[[09] ThJ2-2] Invited Talk [Online] 14:25-14:50****From Hidden Metal-Insulator Transition to Planckian-Like Dissipation by Tuning Disorder in a Nickelate**Qikai Guo and Beatriz Noheda (*Univ. of Groningen, Netherlands*)**[[09] ThJ2-3] 14:50-15:05****Investigation on the Hydrophilic Nature of HfO<sub>2</sub> Thin Films Prepared by Atomic Layer Deposition**Sangyoon Lee, Hwi Yoon, Yujin Lee, Sanghun Lee, and Hyungjun Kim (*Yonsei Univ., Korea*)**[[09] ThJ2-4] 15:05-15:20****Oxidant Effect on HfO<sub>2</sub> Film Properties using Newly Synthesized Cp-Based Hf Precursor by Atomic Layer Deposition**Seonyeong Park, Hwi Yoon, Yujin Lee, Sanghun Lee, Hyunho Lee, Seung-Min Chung, and Hyungjun Kim (*Yonsei Univ., Korea*)